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Improving nano-positioning for Ptychography through error minimisation and Machine Learning

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Ptychography is an advanced imaging technique. Its latest developments have allowed for exceptionally high resolution in X-ray microscopy reaching under 5 nm in synchrotron beamlines. Among its experimental requirements (i.e. coherent beam) there is mechanical precision in moving the sample during scanning. Special setups using precise sample stages with nanopositioning and advanced interferometers are important; however, positioning errors still remain a problem for many operating laboratories. The knowledge of the precise physical position that the data were acquired impacts the resolving power of the technique. In this poster presentation we highlight the latest results of a previously published work that developed a computational workflow aiming at refining the individual probe positions of a ptychography scan. We critically assess the Structural Similarity Index as a suitable metric for evaluating the registration in alignment of individually reconstructed probes and suggest the use of a Machine Learning strategy for probe alignment.

X-Ray Ptychography and mechanical precision problem

Ptychography is an advanced super-sampling imaging technique that allows for exceptionally **high resolution microscopy** (< 5 nm)

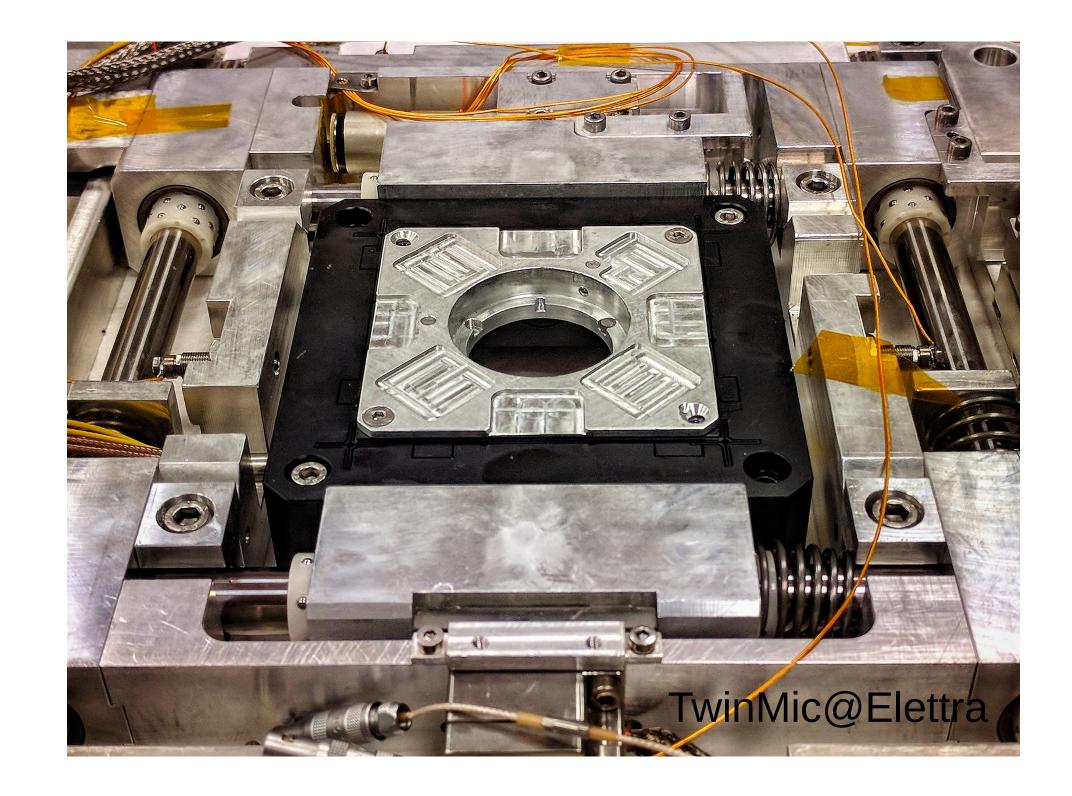
Computationally intensive

X-Ray Diffraction

Microscopy

MSSIM

Sample stage mechanical precision impacts resolving power of the technique.



- Guess a correct alignment that maximises a quality metric.
- Open Source, Python,
 PyQTGraph

